



FOR IMMEDIATE RELEASE

RASIRC Presents Results of Silicon Nitride Deposition Study at AiMES Conference

San Diego, Calif – September 30, 2018–RASIRC will present nitride deposition research results at AiMES 2018 held September 30-October 4, 2018 in Cancun, Mexico. RASIRC Chief Technology Officer Daniel Alvarez, Jr. will present data from experiments using hexacholorodisilane (HCDS) and hydrazine on a Si-H substrate at 250-400°C. SiN films with low impurities were achieved for oxygen (<2%) and chlorine (<1%). The presentation will compare growth rates, film density, refractive index and wet etch rate results at different temperatures.

“Plasma approaches do not meet conformality requirements for many applications with HAR and 3D structures,” said Jeffrey Spiegelman, RASIRC President and Founder. “Alternatively, growth of high quality films by thermal atomic layer deposition is being enabled by anhydrous hydrazine at low temperatures.”

Technical Presentations

Spiegelman and Alvarez are co-authors of one presentation and contributing authors to another presentation at AiMES 2018:

“Low Temperature Thermal ALD TiNx and TaNx Films from Anhydrous N2H4,” 9:40
Monday October 1, Universal 12 Expo Center
S. Wolf, M. Breeden, M. Kavrik, J.H. Park, A.C. Kummel (University of California, San Diego),
D. Alvarez, R. Holmes, J. Spiegelman (RASIRC)

“Low Temperature Thermal ALD of Silicon Nitride Utilizing a Novel High Purity Hydrazine Source,” 9:20 Tuesday October 2, Universal 16 Expo Center
D. Alvarez Jr., K. Andachi, J. Spiegelman (RASIRC), A.T. Lucero, A. Kondusamy, S.M. Hwang, X. Meng, H. Kim, J. Kim (University of Texas at Dallas)

About BRUTE Hydrazine

BRUTE[®] Hydrazine enables low temperature ALD (sub-400°C) and low resistivity. BRUTE Hydrazine gas is virtually water free and has a relatively high flash point for safer handling. Highly reactive, BRUTE Hydrazine creates uniform nitride deposition for advanced materials.

About RASIRC

RASIRC specializes in products that generate and deliver gas to fabrication processes. Each unit is a dynamic gas plant in a box—converting common liquid chemistries into safer and reliable gas flow for most processes. RASIRC technology delivers water vapor, hydrogen peroxide gas and hydrazine gas in controlled, repeatable concentrations. RASIRC gas delivery systems, humidifiers, and closed loop humidification systems are critical for many applications in semiconductor, photovoltaic, pharmaceutical, medical, biological, fuel cell, and power industries. Call 858-259-1220, email info@rasirc.com or visit <http://www.rasirc.com>.

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